

Mask Blank and Making Method

ABSTRACT

5 In a mask blank comprising a transparent substrate and
a single layer or multilayer film formed thereon, the film is
formed only on the front surface of the substrate, but not on
the side surface, chamfer, front surface-chamfer boundary,
and back surface-chamfer boundary. The mask blank contains
10 few particle defects, especially the number of particle
defects with a certain size is zero.

Figure 2